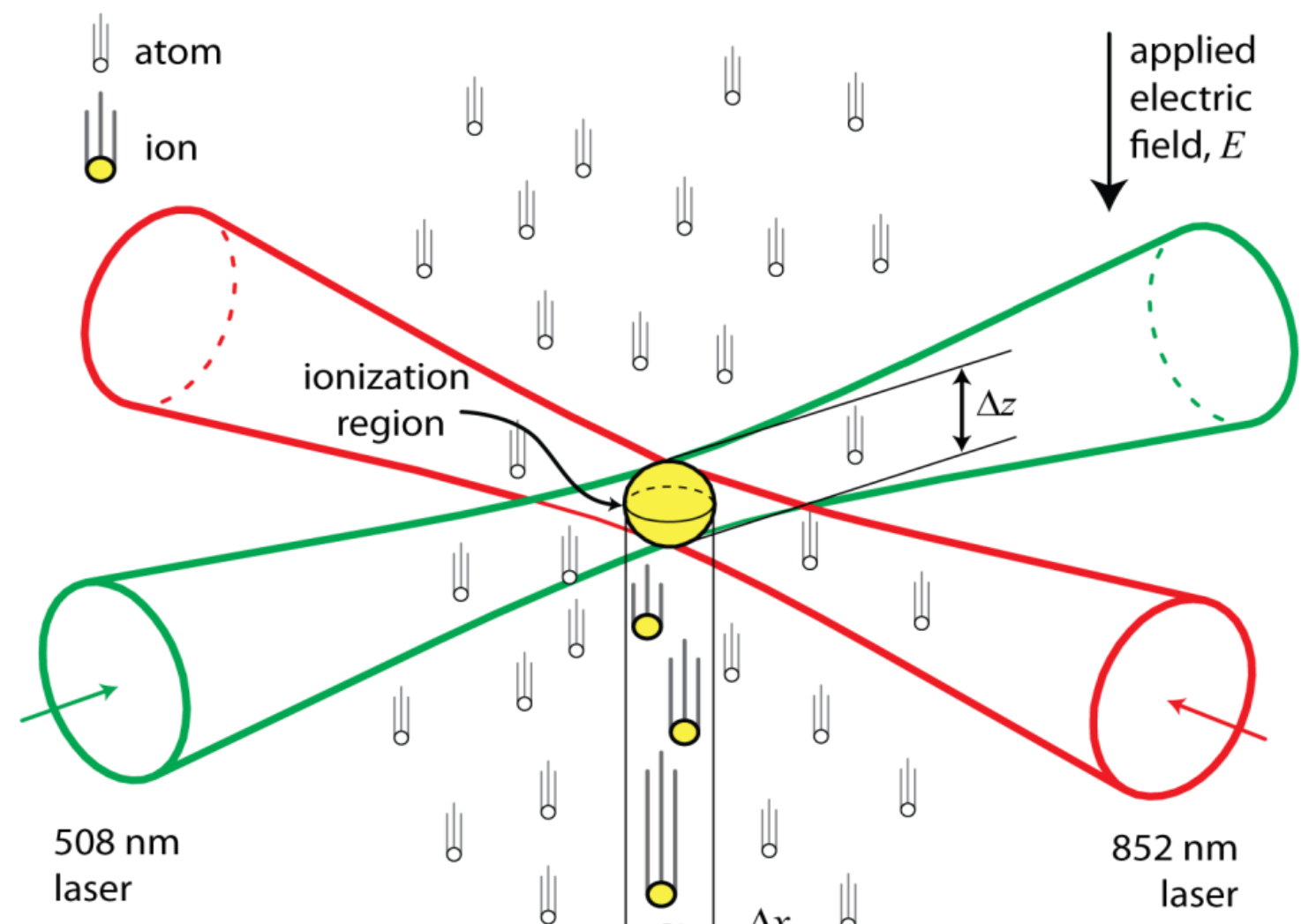


Cs⁺ Low Temperature Ion Source

A high-brightness, low-energy-spread ion source for SIMS

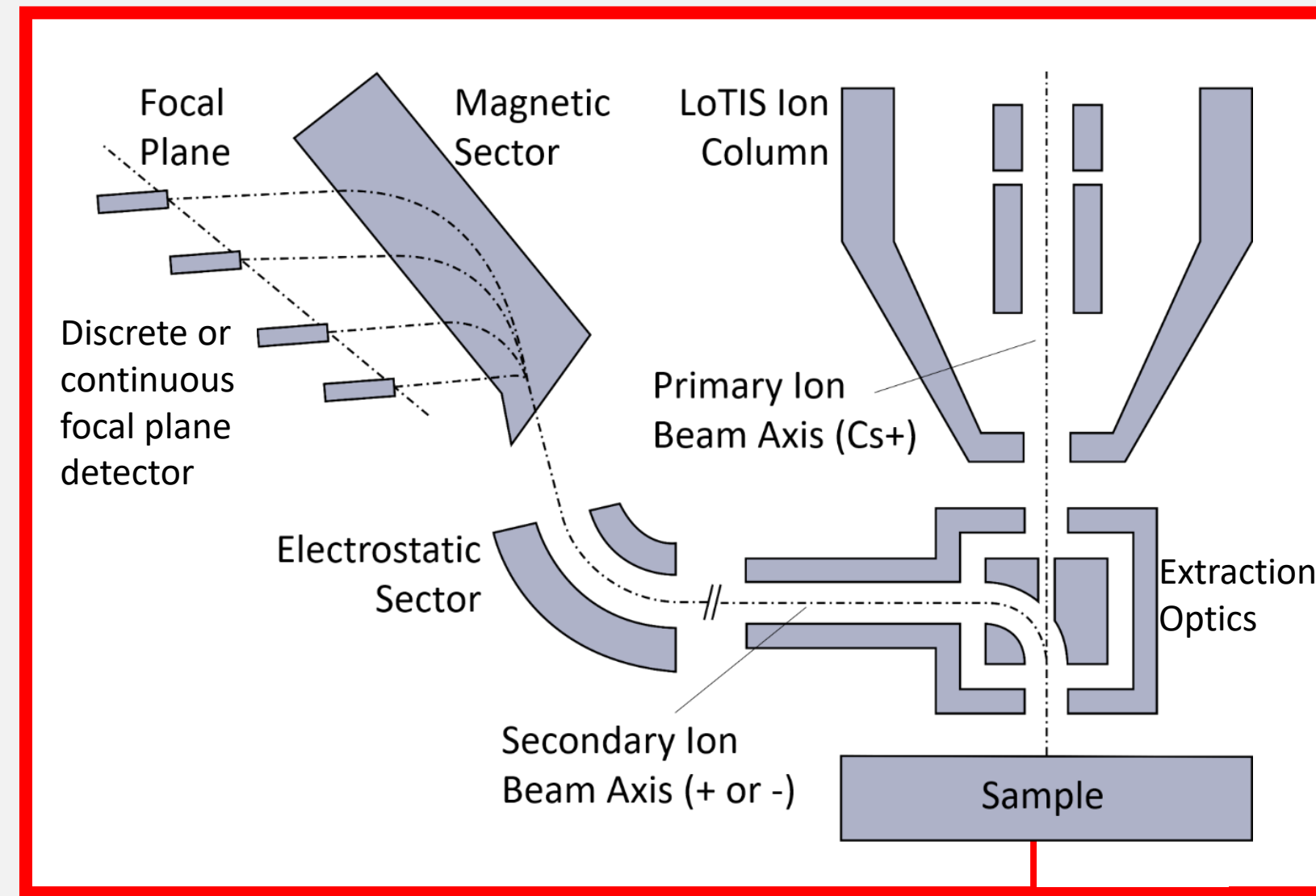
Brenton Knuffman & Adam V. Steele
zeroK NanoTech Corporation, Gaithersburg, Maryland, USA

Cs⁺ LoTIS



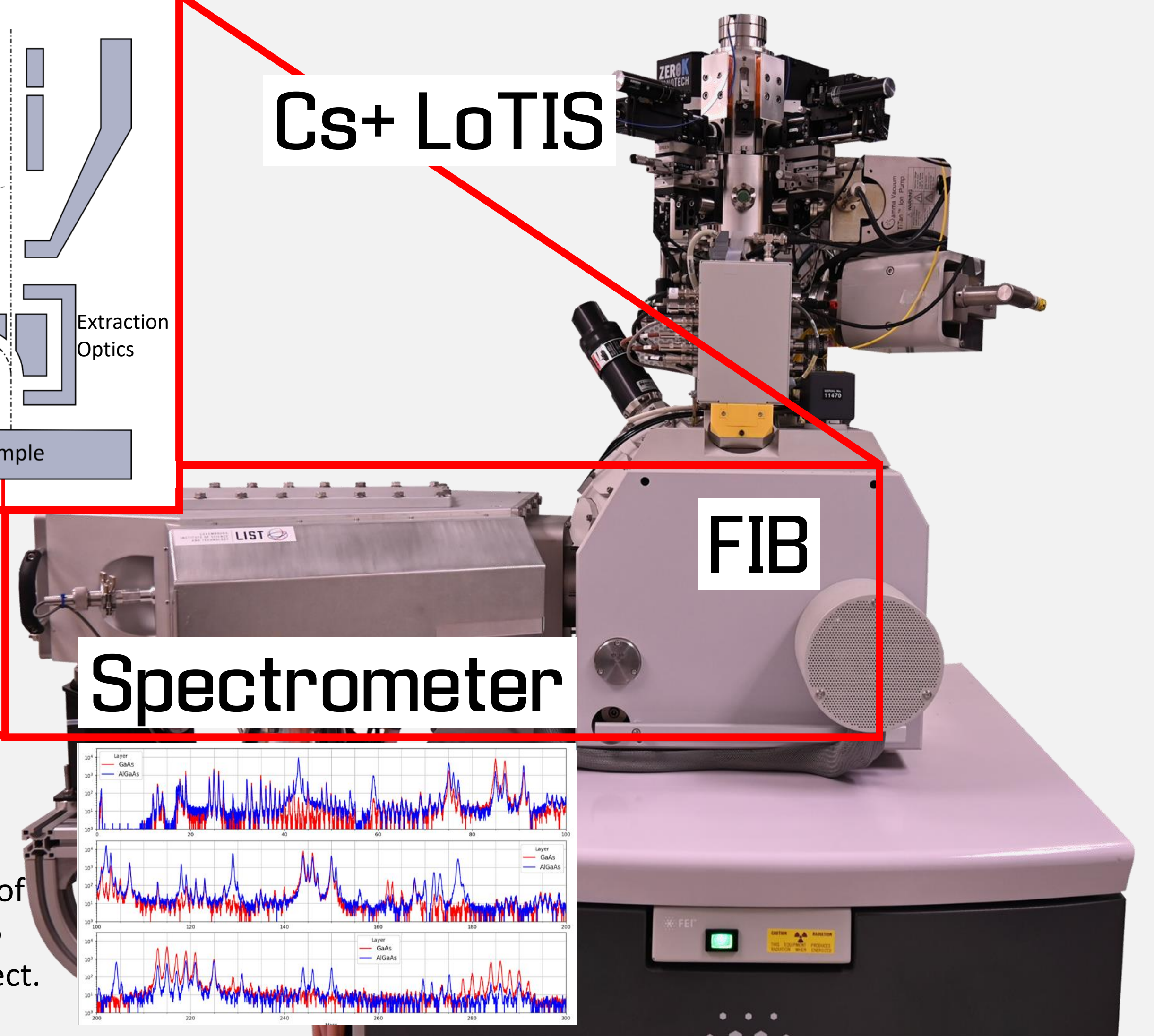
Ions are created in a laser-cooled atomic beam as it flows through the intersection of photoionizing laser beams and accelerated in an applied electric field.

The resulting Cs⁺ beam has exceptional properties:
 < 3 nm spot @ few pA Energy Spread < 1 eV
 < 1 μm spot @ 5 nA Current up to 5 nA



Cs⁺ LoTIS (zeroK) and SIMS spectrometer (LIST) on a Nova series FIB (FEI)

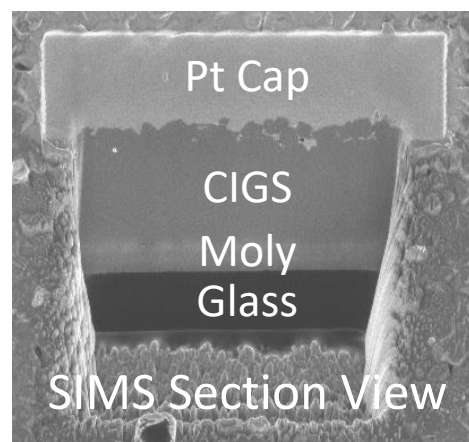
The magnetic sector spectrometer has $m/\Delta m \sim 400$ and is equipped with a continuous focal plane detector capable of acquiring an entire mass spectrum (up to 300 amu) at once with no duty cycle effect.



SIMS Analysis Examples

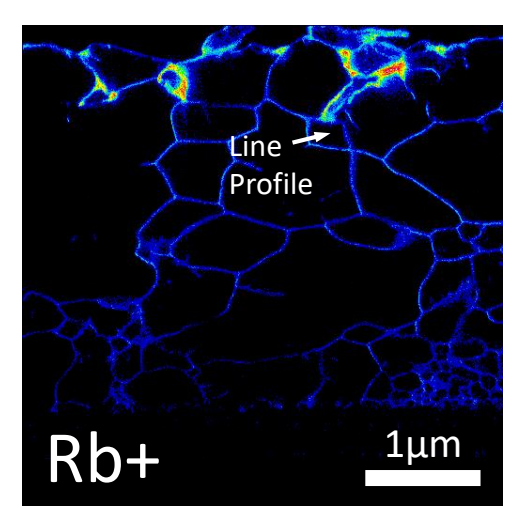
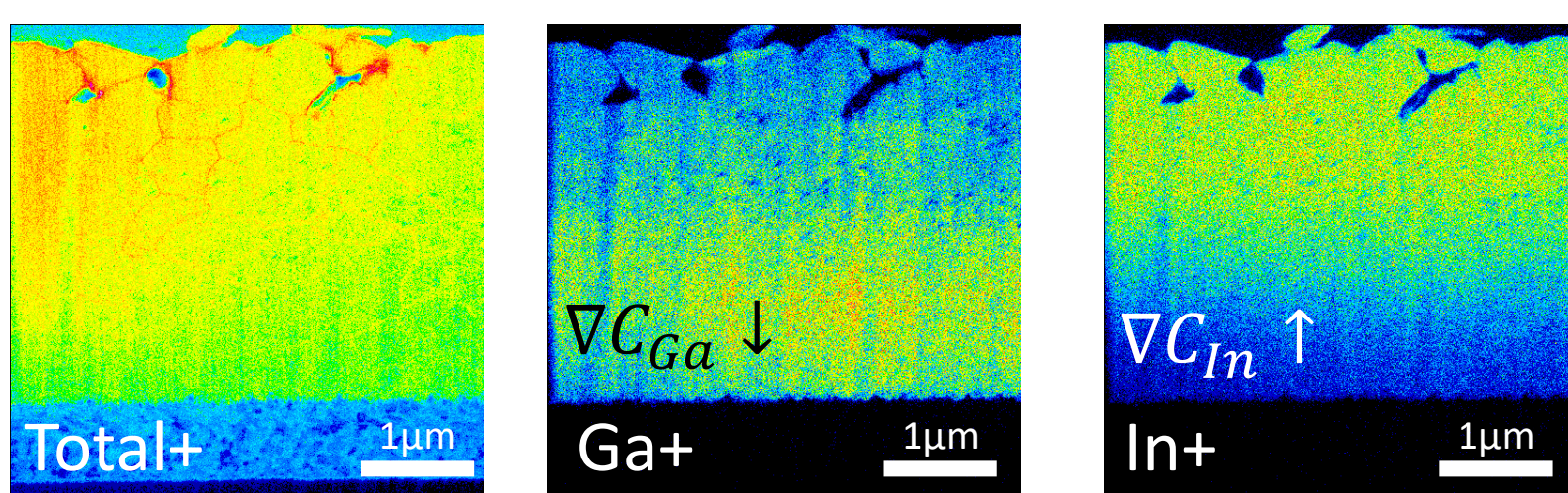
Solar Cell

CIGS Cu(In,Ga)Se₂ – Rb doped Absorber

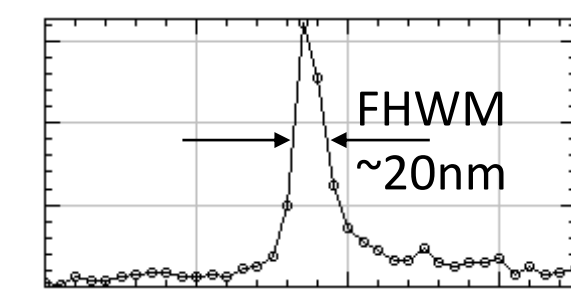


Integrated sample prep and analysis with Cs⁺ LoTIS ion beam

- Deposit Pt Cap, Machine Section
- Acquire SE and SIMS images

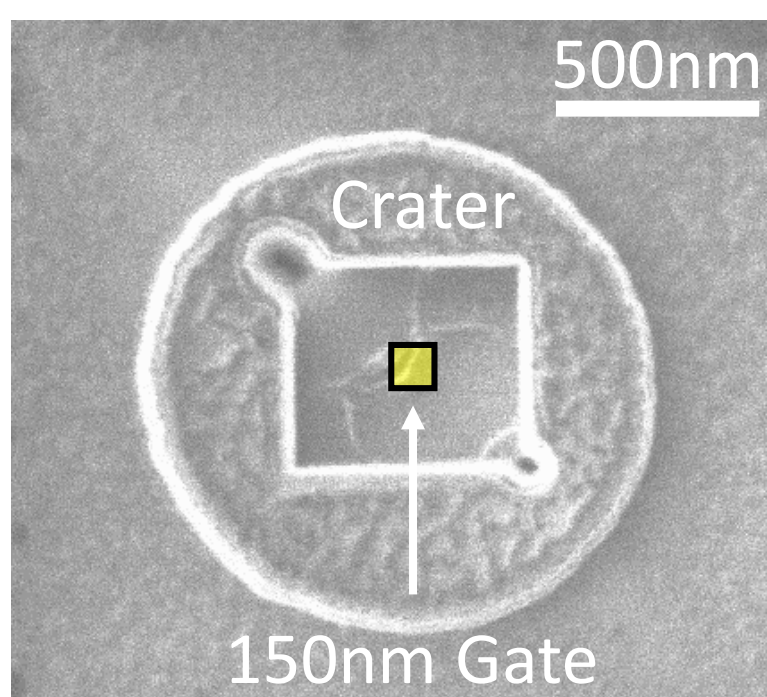


Apparent width of Rb at grain boundary



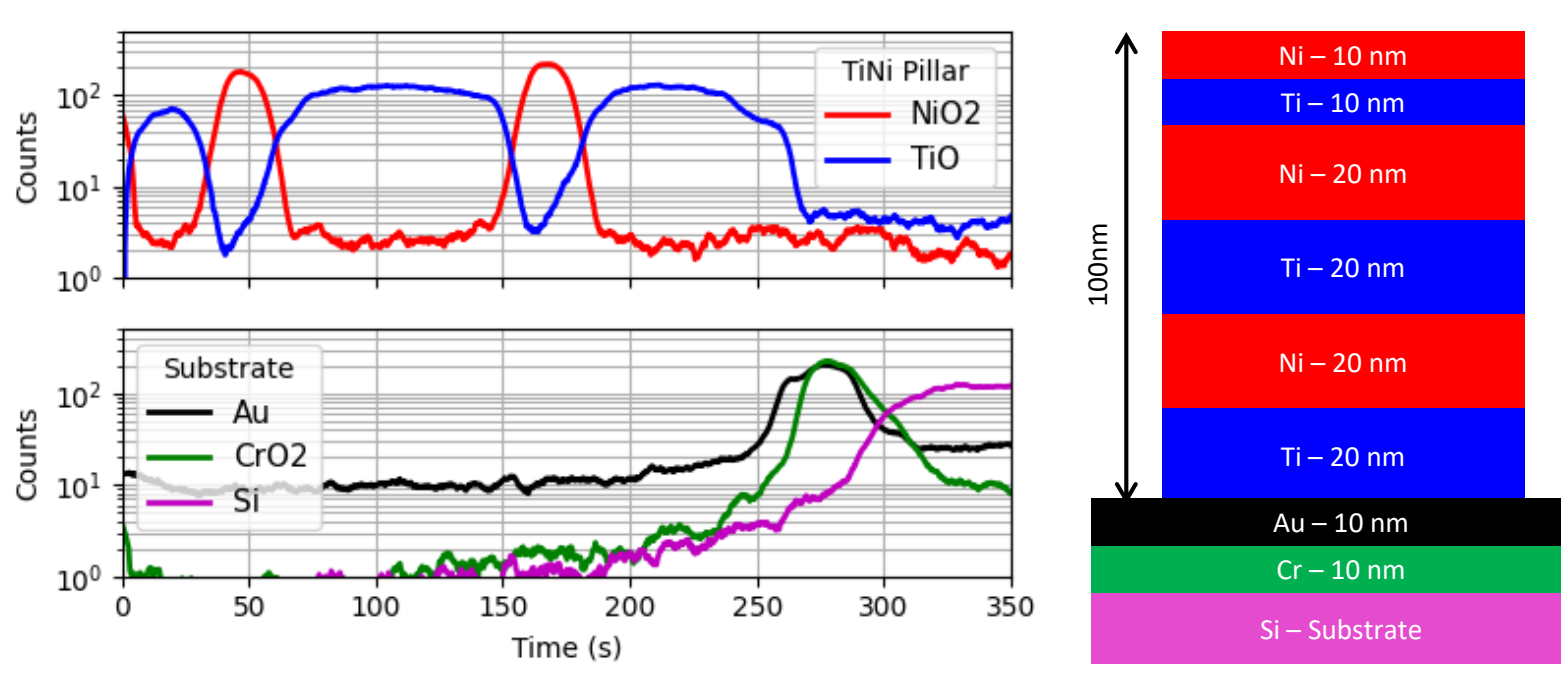
TiNi Pillars

3D movie



Highly localized depth profile performed at 8kV from a square area gate with 150nm sides.

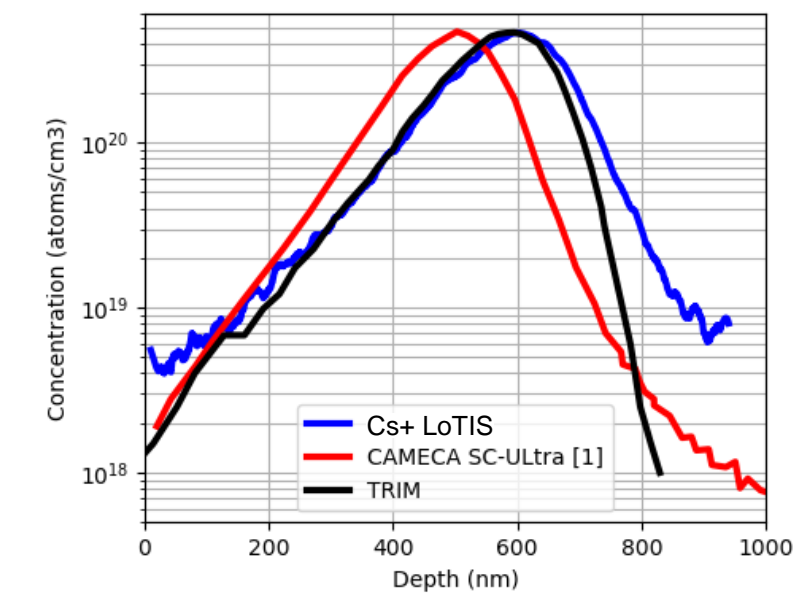
Good SNR, few-nm depth resolution



Boron in Silicon

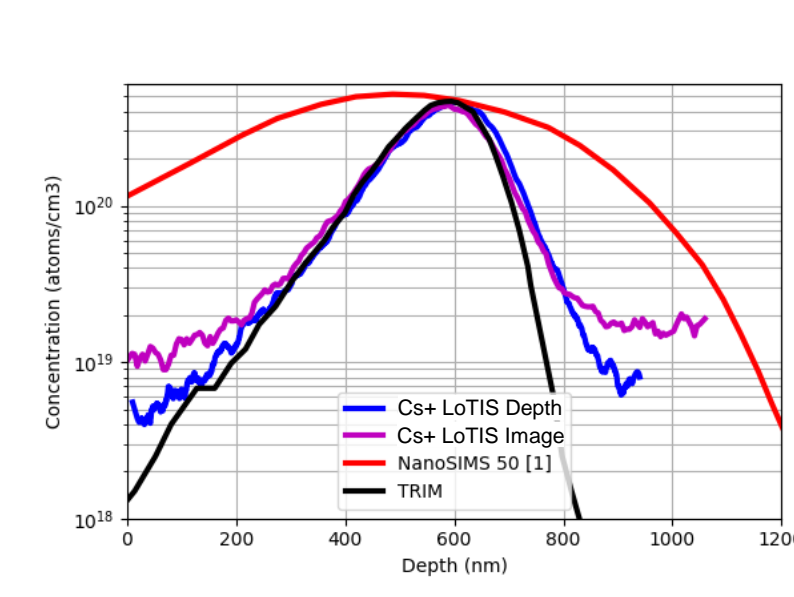
Implanted B in Si @ 190 kV; dose 10¹⁶ ions/cm²

Depth Profile



	Cs+ LoTIS	SC Ultra
Primary Ion	Cs+	O ₂ ⁺
Energy	16kV	4.5kV
Current	25pA	8500pA
Area	4.2μm x 4.2μm	?
Secondary Ion	¹¹ B ²⁺	¹¹ B ⁺

Section View Profile

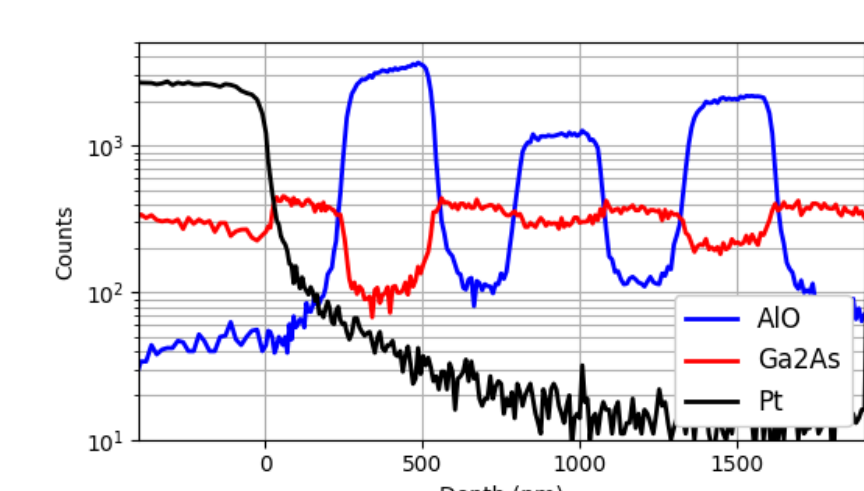
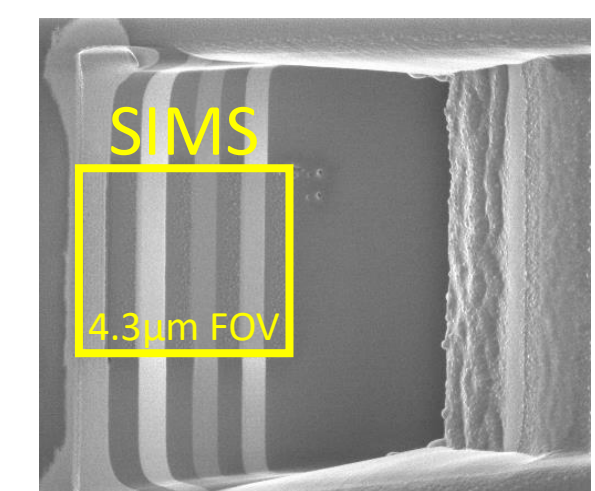


	Cs+ LoTIS	NanoSIMS 50 [1]
Primary Ion	Cs+	O ₂ ⁺
Energy	16 kV	16 kV
Current	1.6 pA	12 pA
Secondary Ion	¹¹ B ²⁺	¹¹ B ⁺

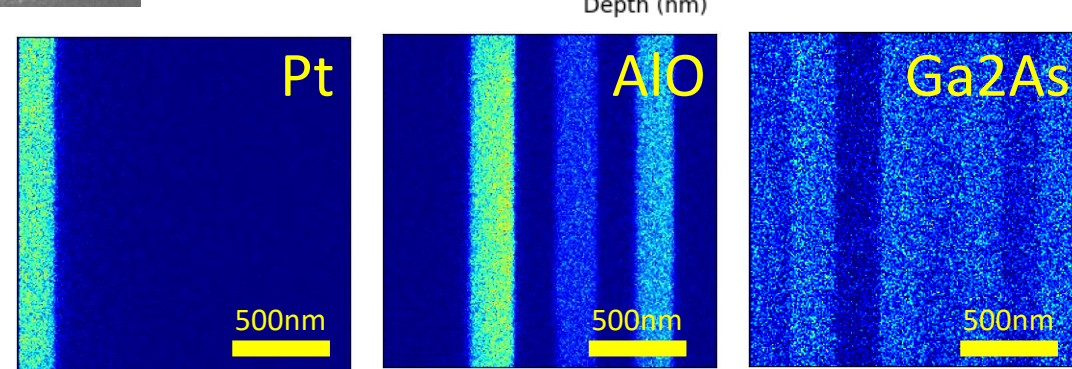
[1] Eswara, et al. MRS COMMUNICATIONS. Volume 9, Issue 3 (2019). 10.1557/mrc.2019.89

AlGaAs Multilayer

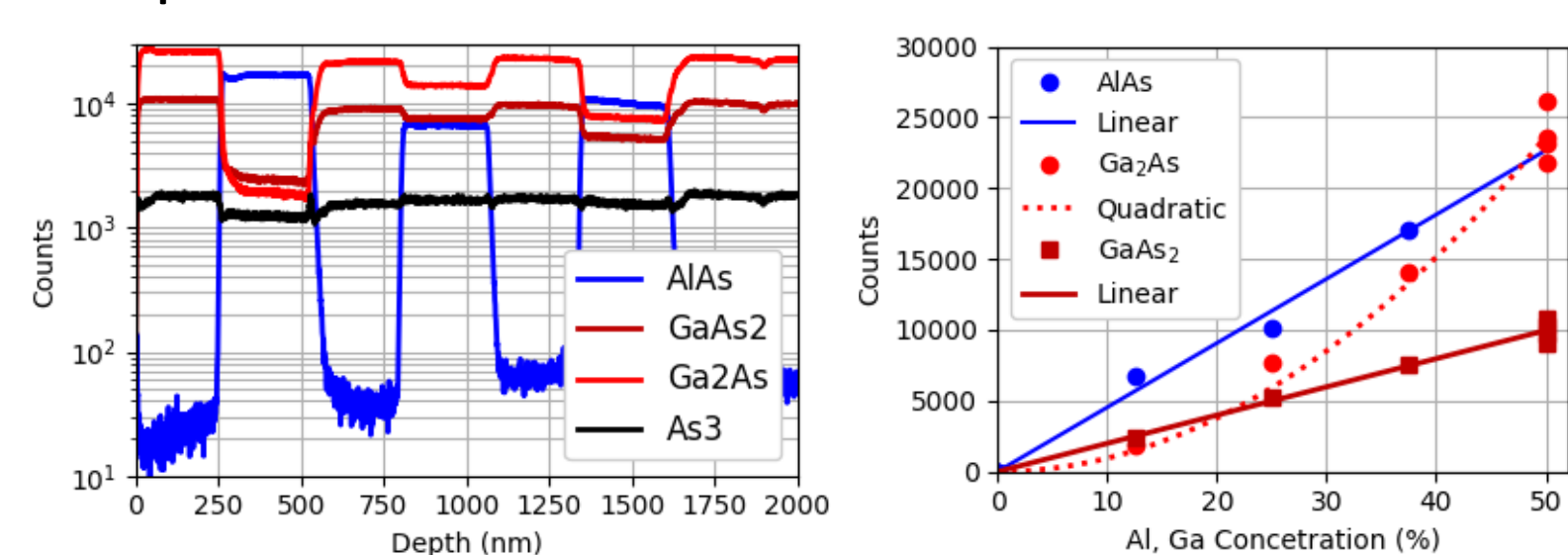
Section View Profile



Alternating GaAs / AlGaAs layers with varying Al, Ga concentrations

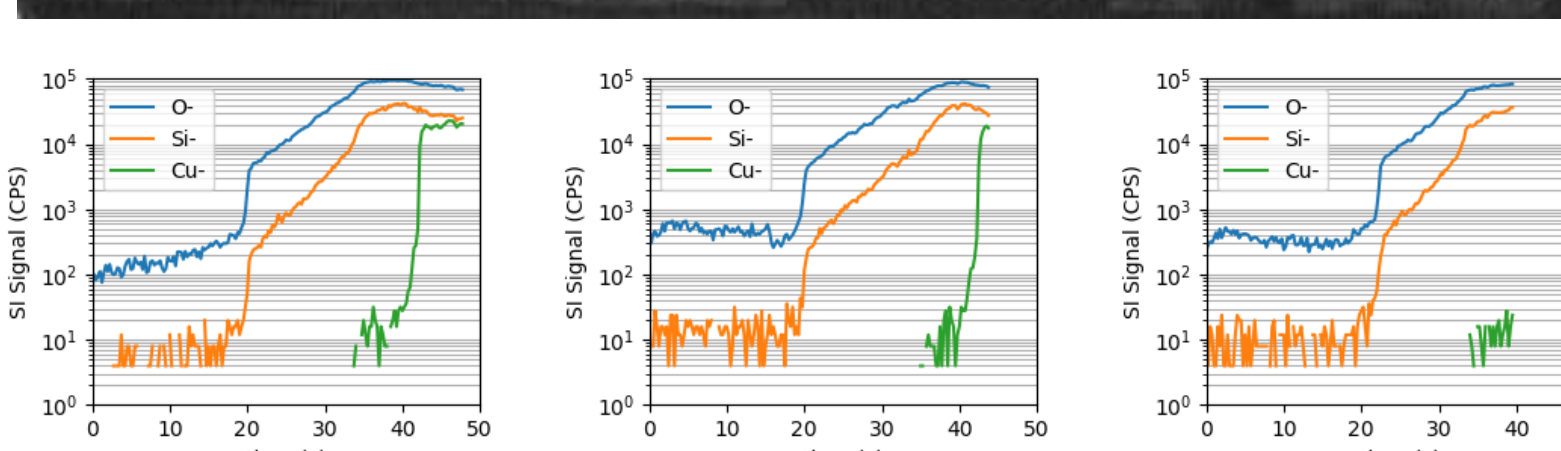
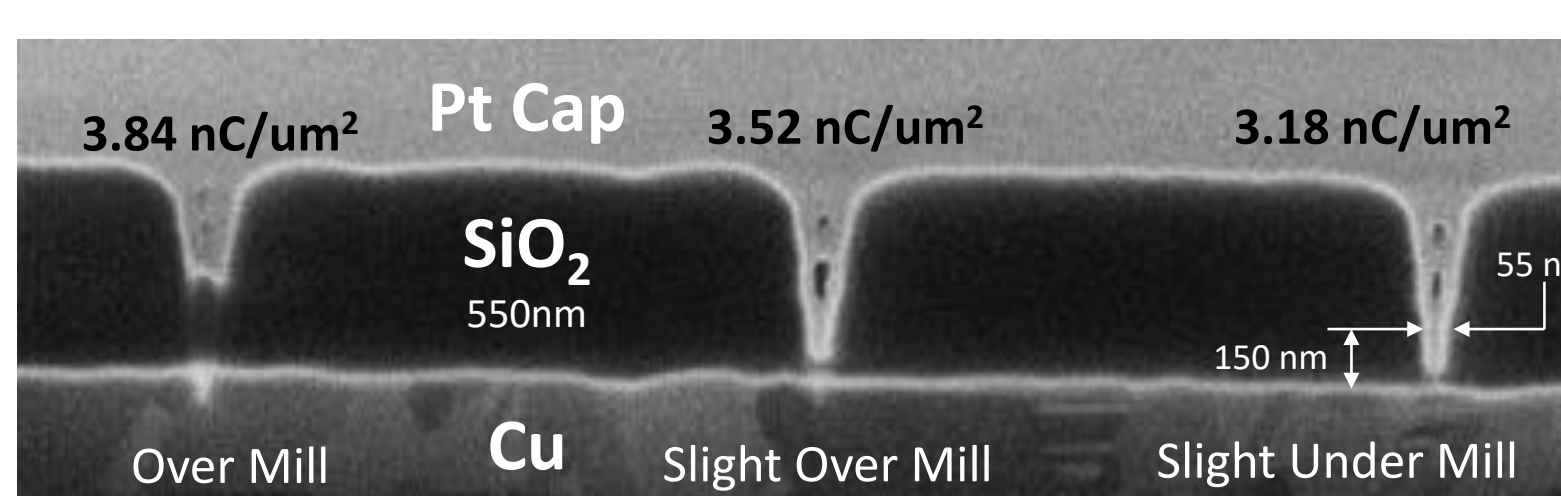


Depth Profile



Nanofabrication Process Control

Endpointing: 50nm wide via, 2.0 pA, 16 kV



Can be difficult to judge transition with SE signals

SIMS signals

- High SNR despite aspect ratio
- Predictive of milling results

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